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January 23, 2003

VIA FACSIMILE

To: Examiner Alanko, Anita K.
Group Art Unit No. 1765
U.S.P.T.O.

Facsimile No.: (703) 872-9311

From: Sean M. McGinn

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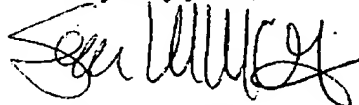
Re: Enclosed § 1.116 Amendment
U.S. Patent Application Serial No. 09/695,028
Our Ref: BUR.089

Dear Examiner Alanko:

Pursuant to our conversation today, enclosed is an After-Final Response which should place the above-referenced case in condition for allowance.

Thank you in advance for your consideration on this case.

Very truly yours,



Sean M. McGinn

SMM/wdc
Enclosure
Total No. of Pages Transmitted: 8

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JAN 24 2003
GROUP 1700

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Jason M. Benz

Serial No.: 09/695,028

Group Art Unit: 1765

Filed: October 24, 2000

Examiner: Alanko, Anita K.

For: **METHOD FOR THIN FILM LASER REFLECTANCE CORRELATION FOR
SUBSTRATE ETCH ENDPOINT**Honorable Commissioner of Patents
Washington, D.C. 20231
BOX AF**RESPONSE UNDER 37 C.F.R. §1.116**

Sir:

In response to the Office Action dated November 21, 2002, please consider the following remarks in the above-identified application:

REMARKS

Claims 1-33, all the claims presently pending in the application, stand rejected under §112, first paragraph, on the ground that allegedly there is no support for isolating the reflective material from an etching process as defined by independent claim 1 (and similarly independent claims 12 and 24) and that the claim amendments of October 9, 2002, "are new matter".

This rejection is respectfully traversed in view of the following discussion.

I. THE CLAIMED INVENTION

Prior to discussing the §112, first paragraph rejection of the claims, Applicant notes for the Examiner that the invention, as defined for example in independent claim 1 (and substantially similarly in independent claims 12 and 23) is directed to a method of etching a substrate which includes measuring a reflectance signal from a reflective material deposited on the substrate as the substrate is being etched.

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